

Fig. 1A formation of base insulating film/  
formation of semiconductor film

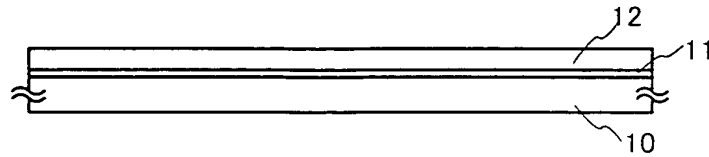


Fig. 1B laser anneal

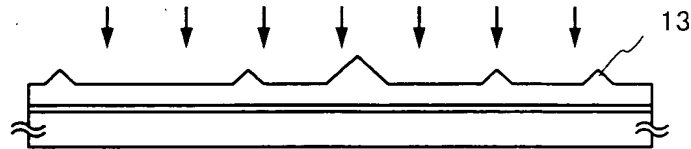


Fig. 1C heat treatment process

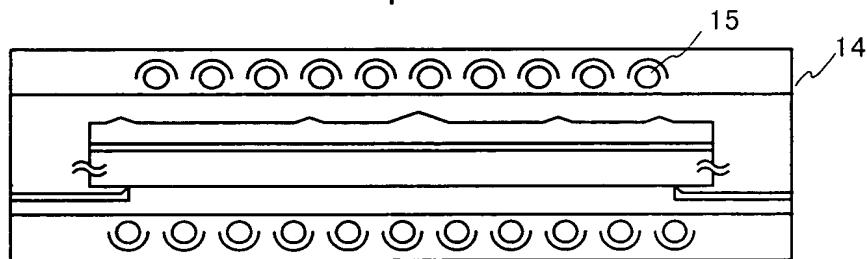


Fig. 1D formation of semiconductor film

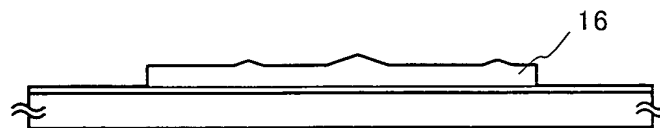


Fig. 2A formation of base insulating film/  
formation of semiconductor film

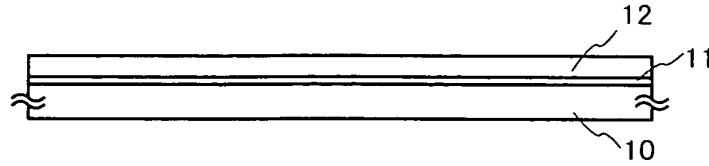


Fig. 2B laser anneal

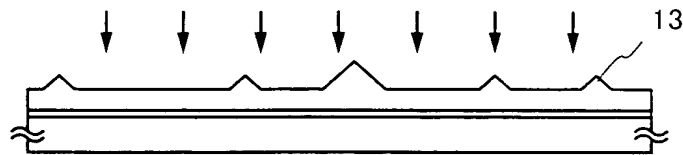


Fig. 2C formation of semiconductor film



Fig. 2D heat treatment process



Fig. 3A formation of base insulating film/  
formation of semiconductor film

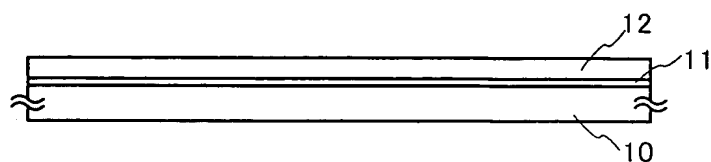


Fig. 3B irradiation of strong light

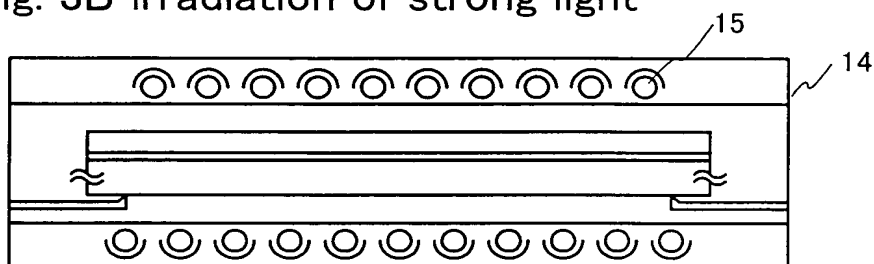


Fig. 3C laser anneal

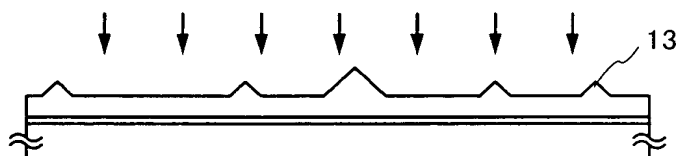


Fig. 3D heat treatment process



Fig. 3E formation of semiconductor film

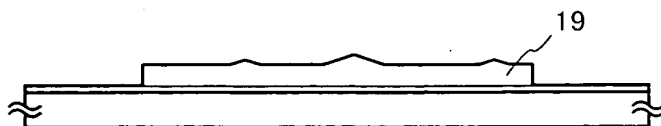


Fig. 4A formation of conductive film/formation of insulating film  
/formation of semiconductor film

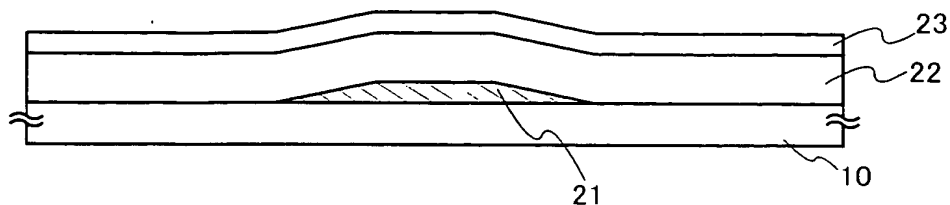


Fig. 4B laser anneal

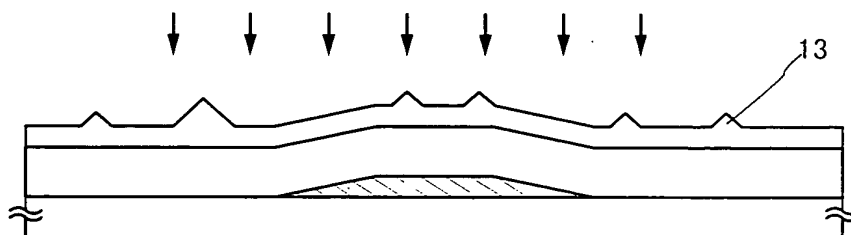


Fig. 4C heat treatment process

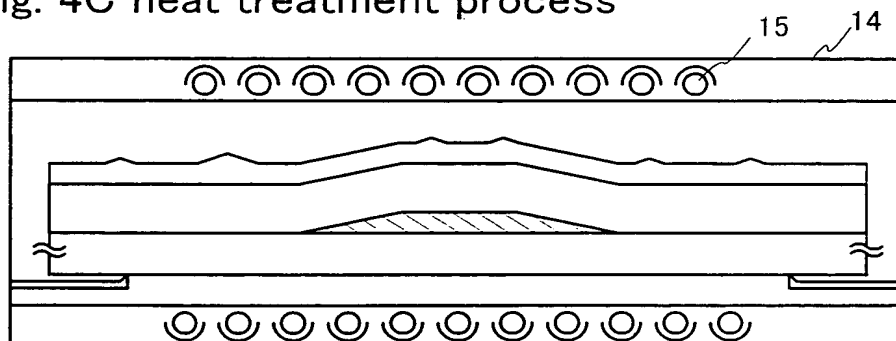


Fig. 4D formation of semiconductor film

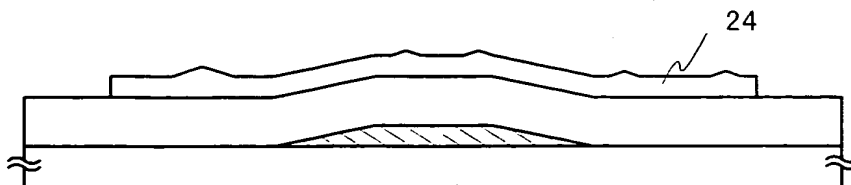


FIG. 5A

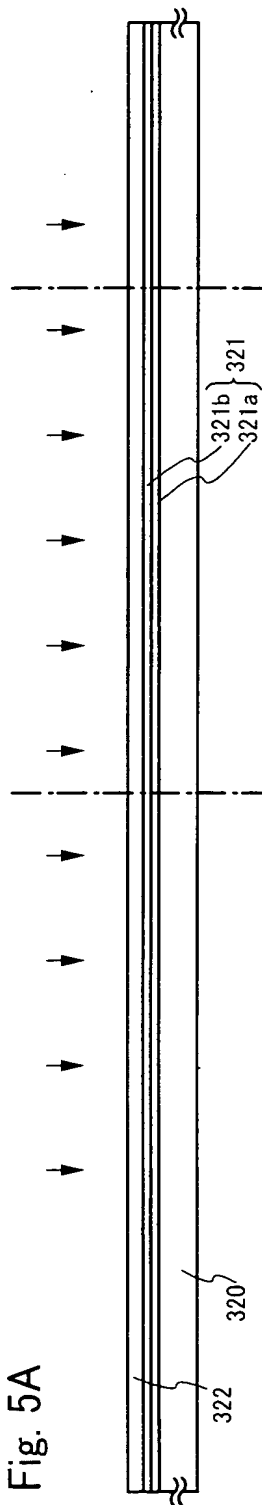


Fig. 5B



Fig. 5C

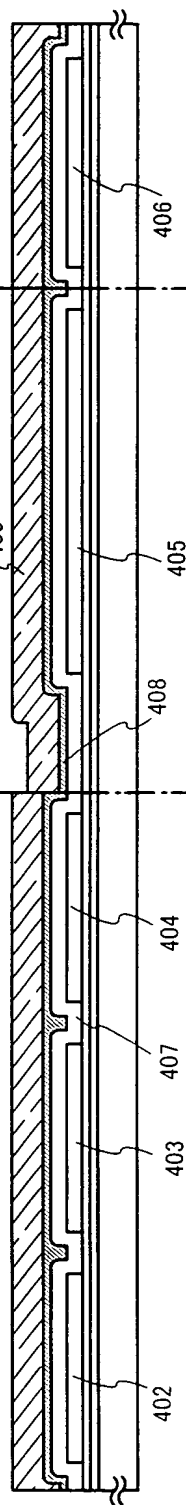


Fig. 5D

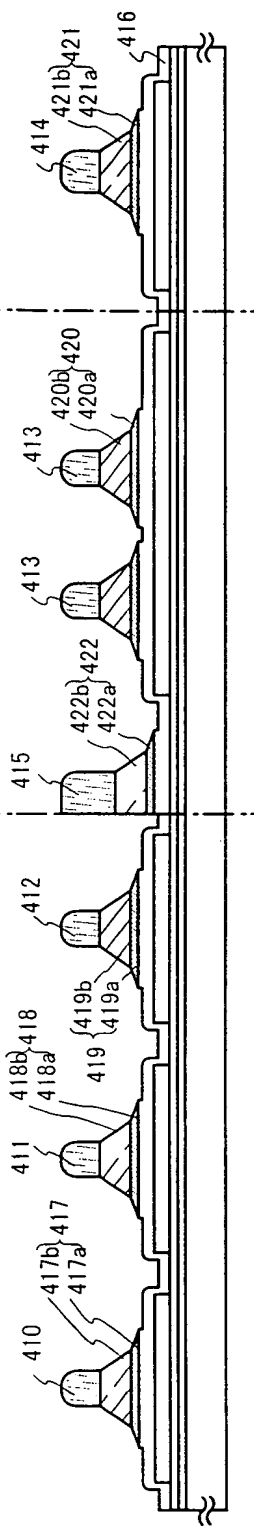


Fig. 6A

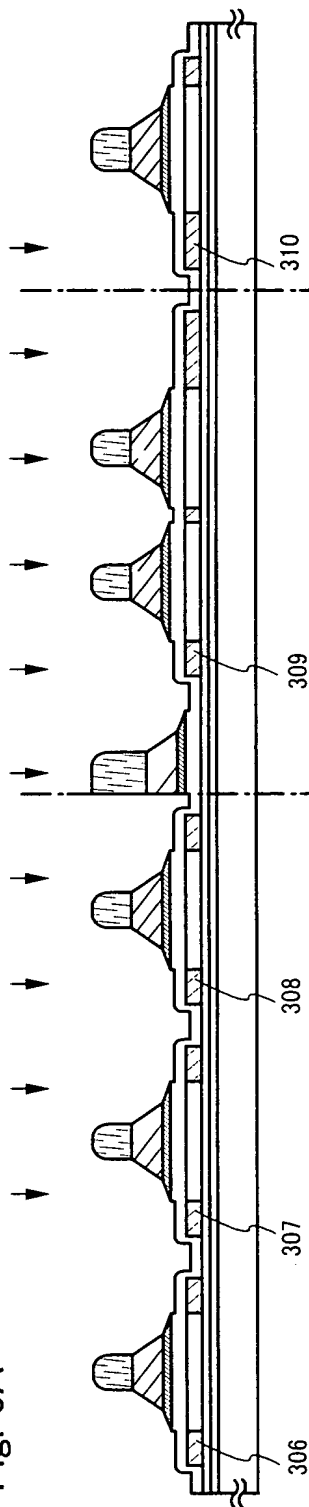


Fig. 6B

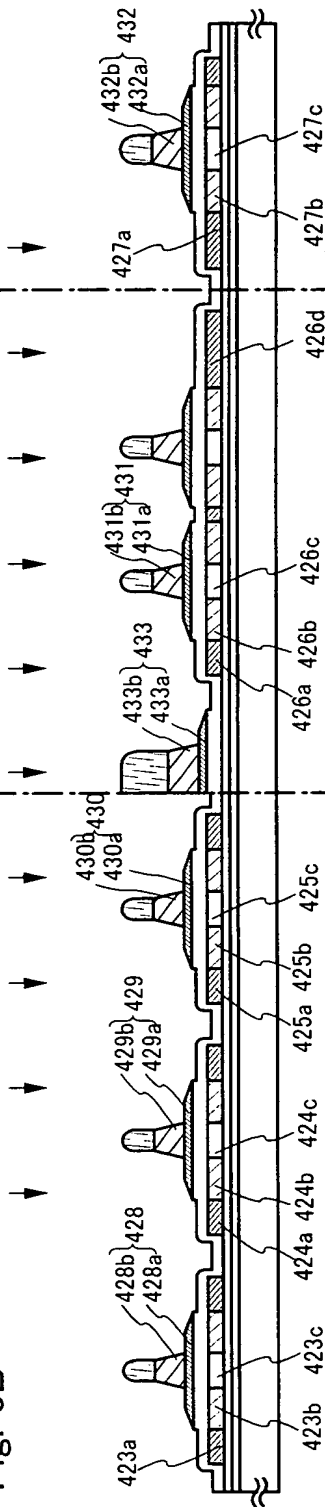
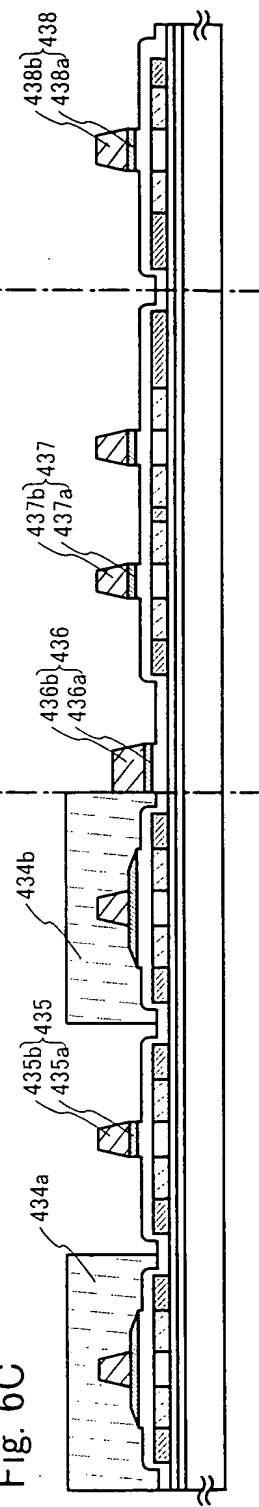


Fig. 6C



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Fig. 7A

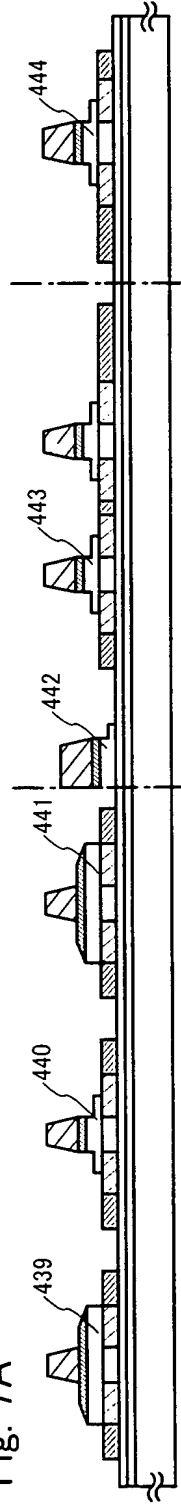


Fig. 7B

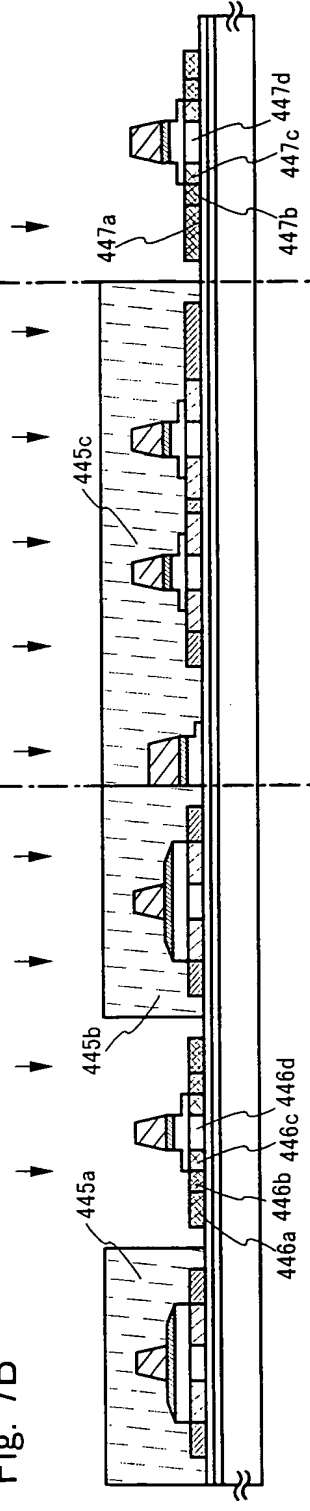


Fig. 7C

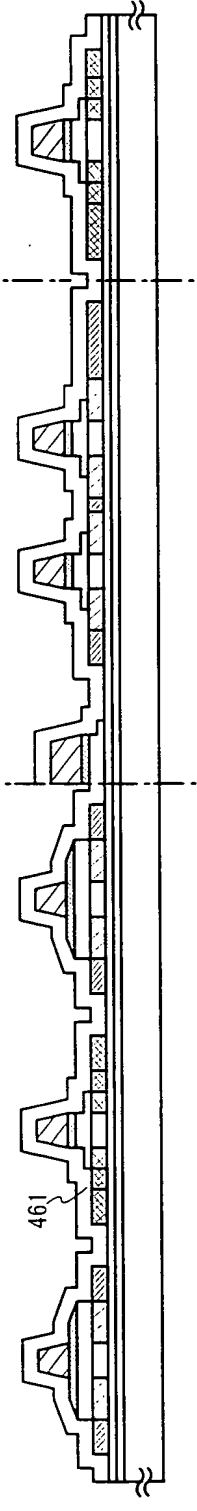
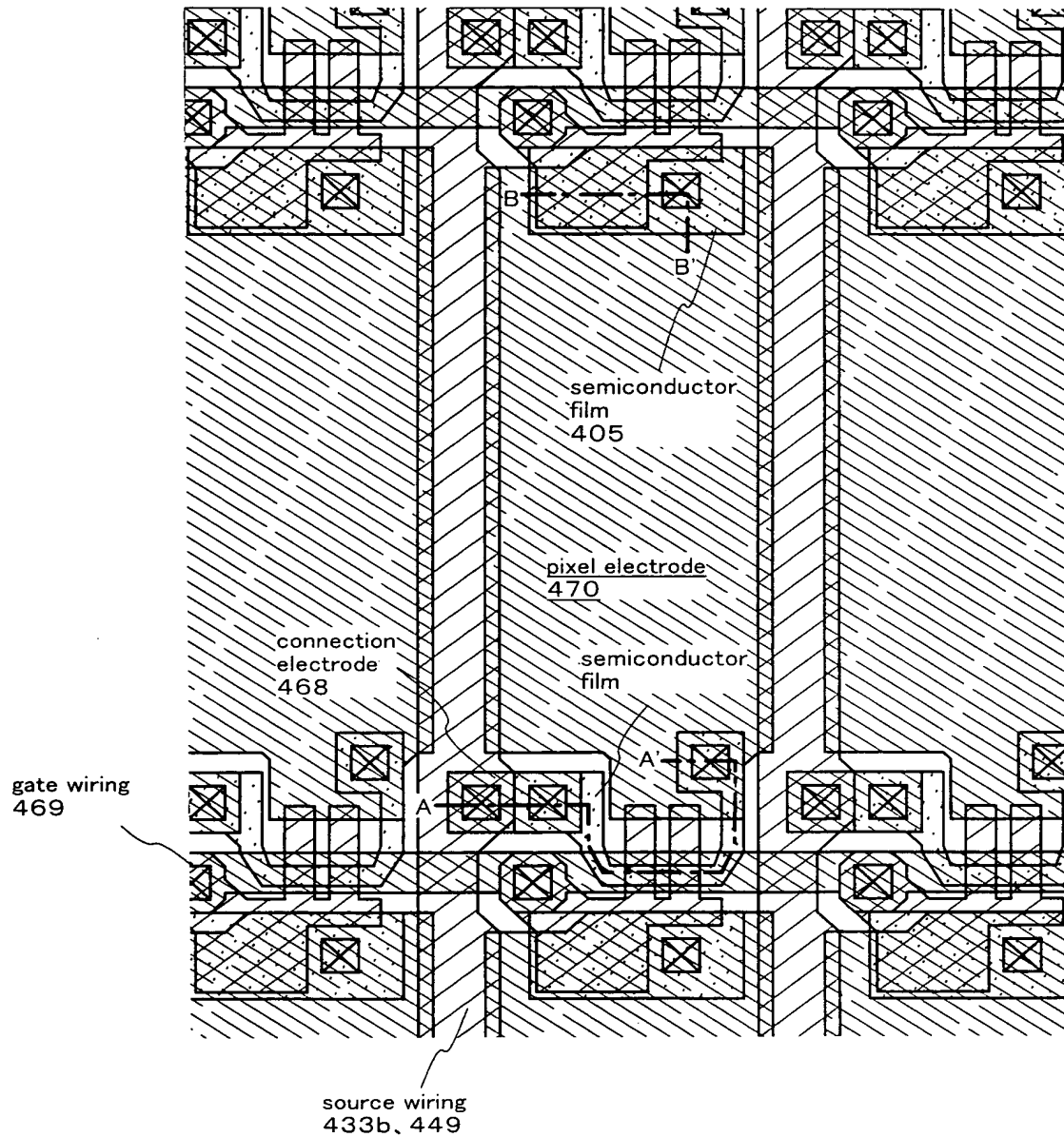






Fig. 9



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FIG. 11

Fig. 11

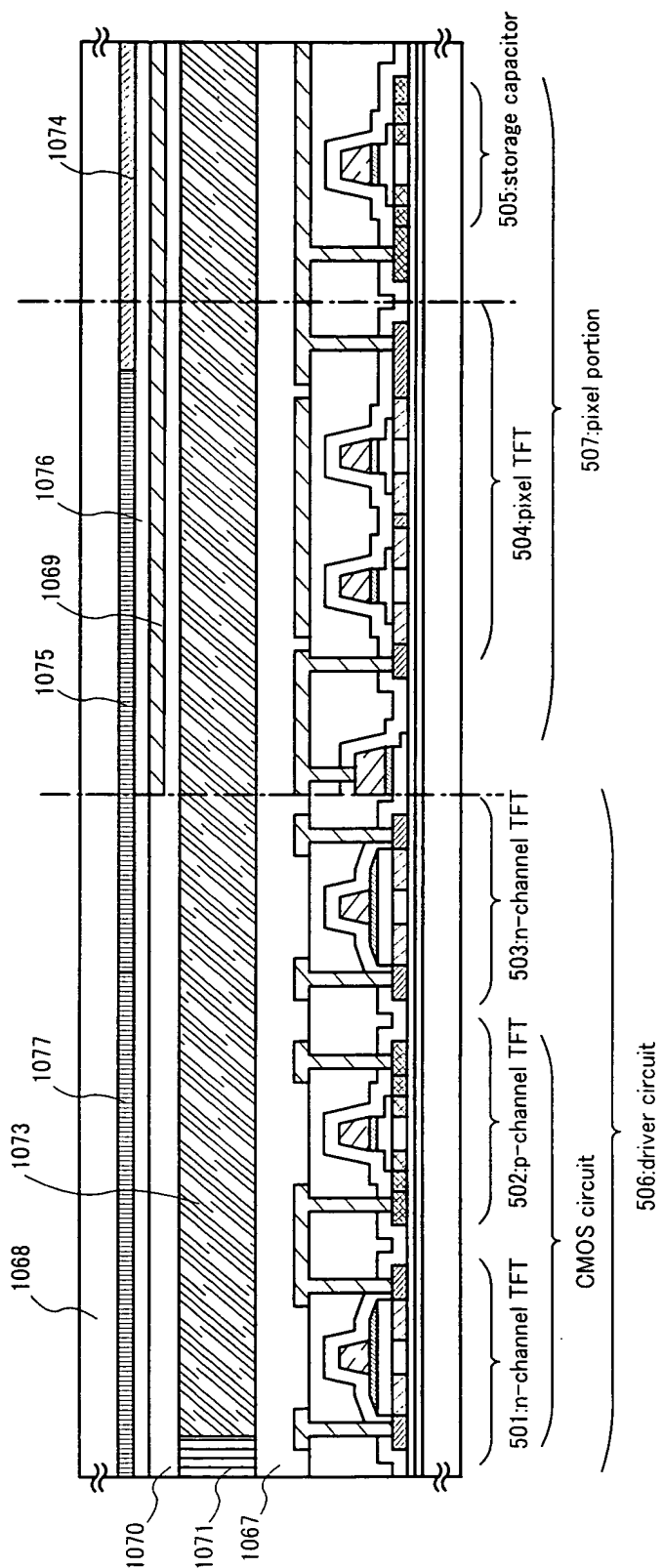


Fig. 12

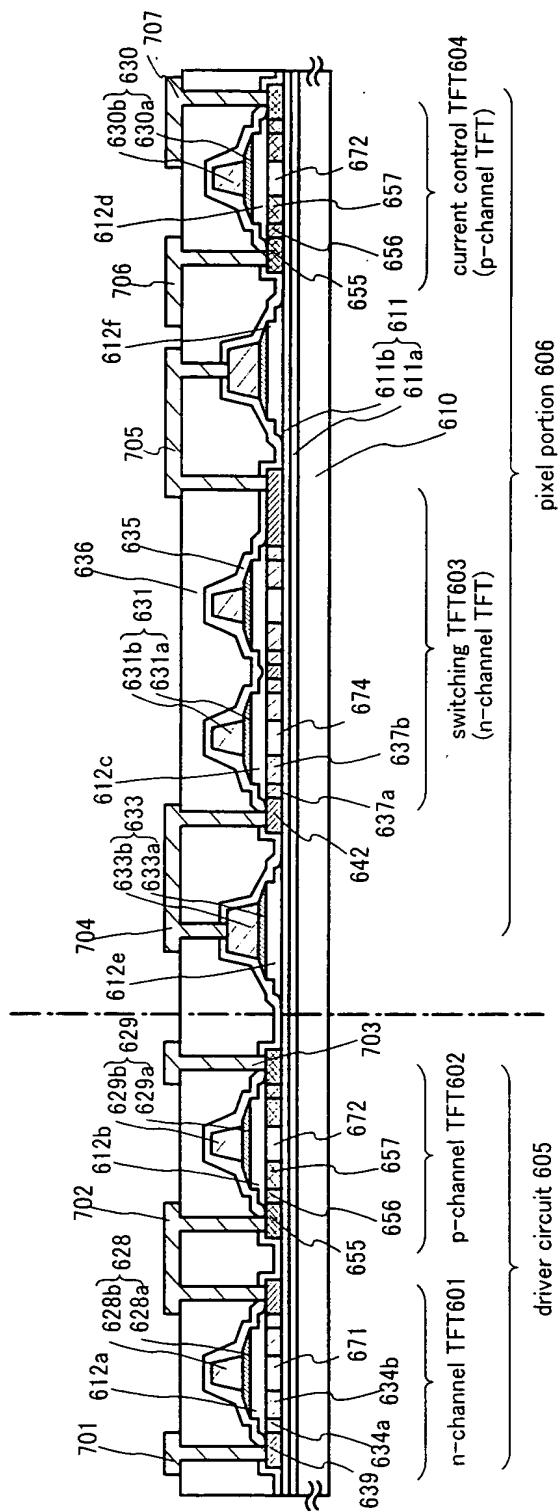
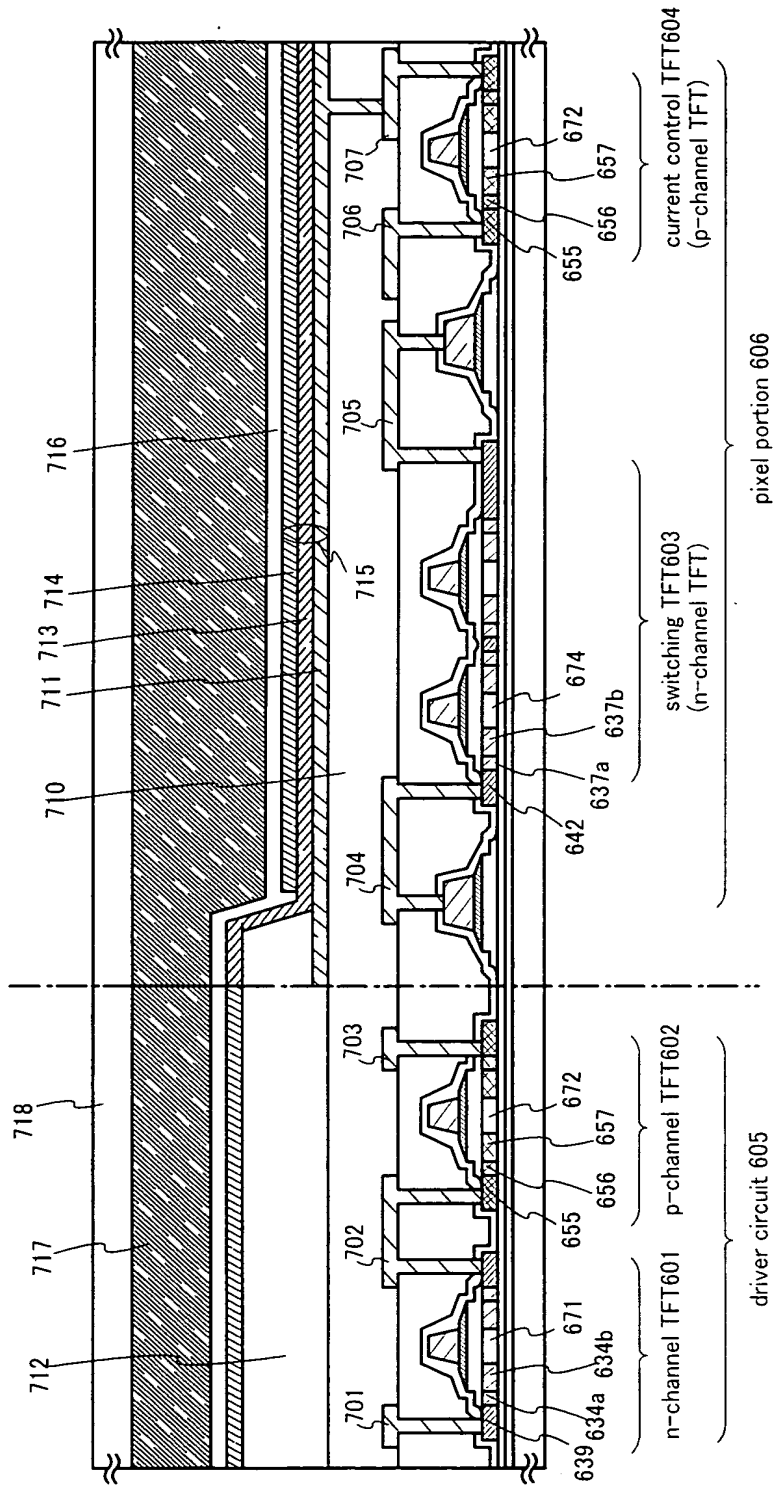


FIG. 13

Fig. 13

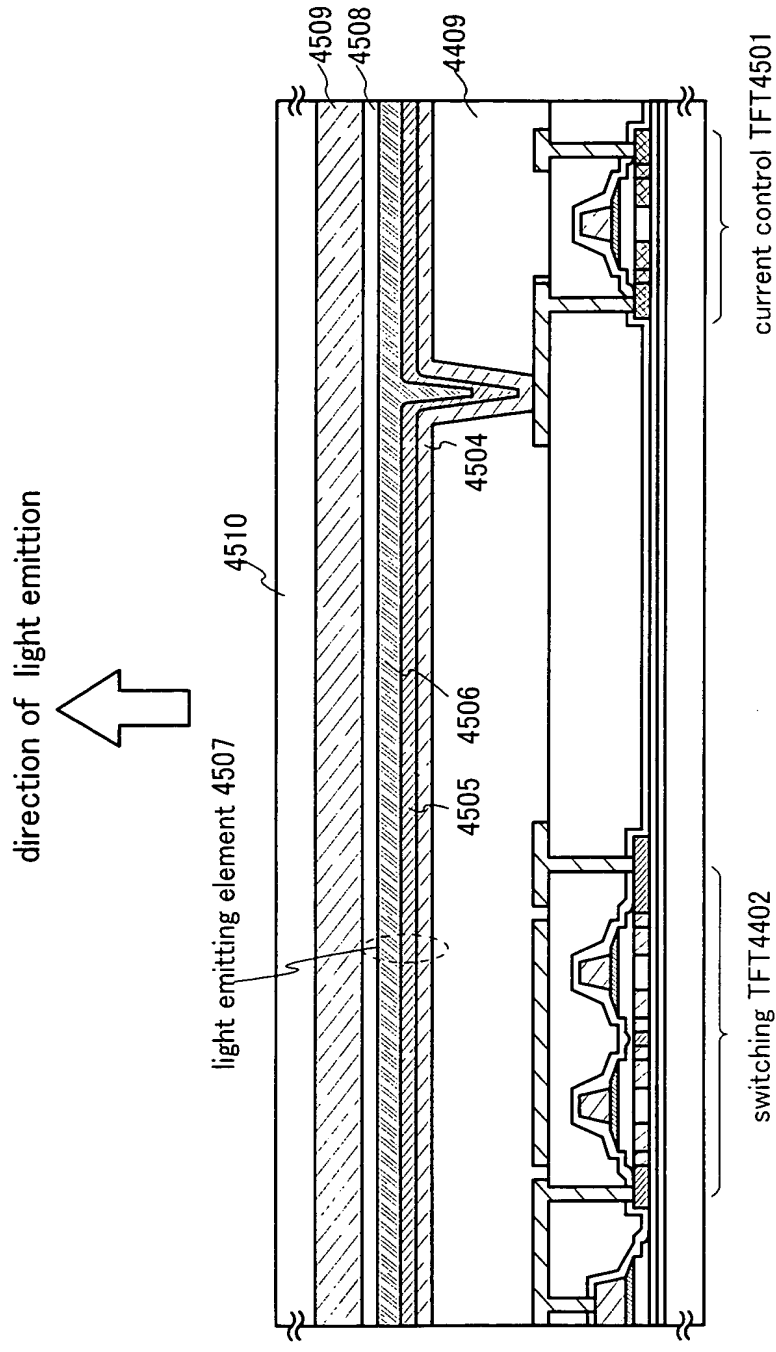




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Fig. 15



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Fig. 16A

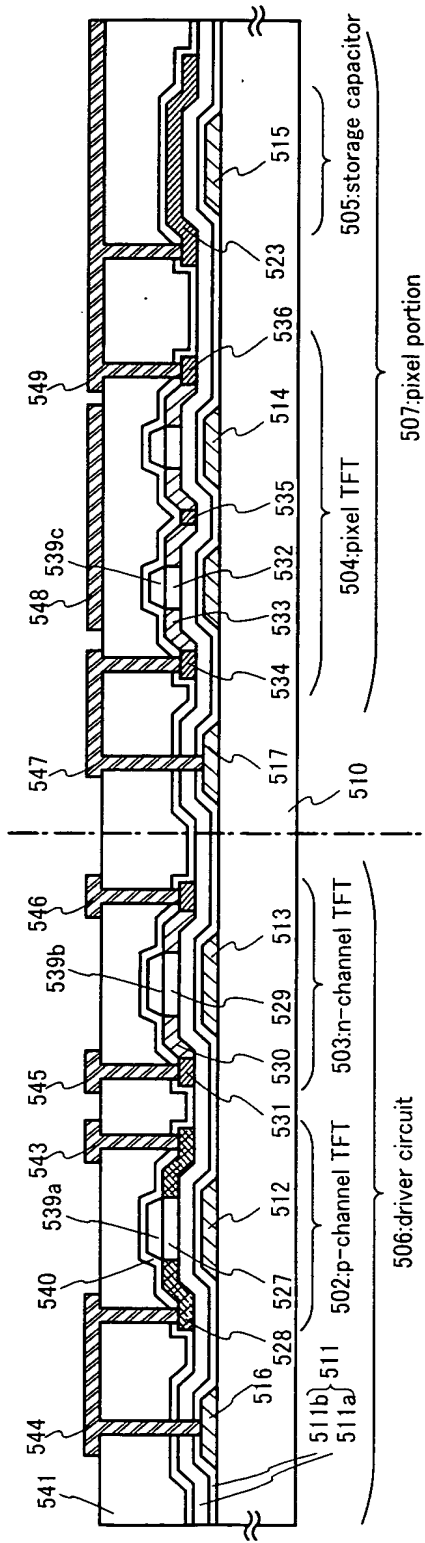
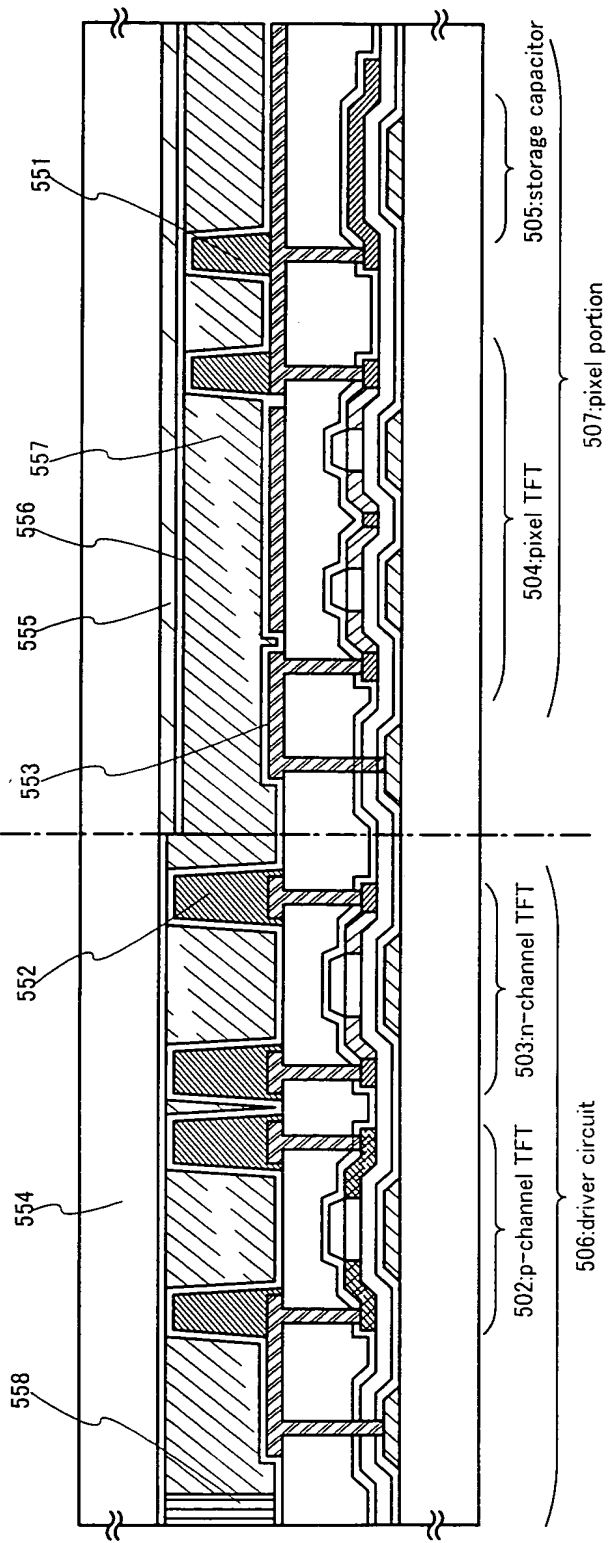


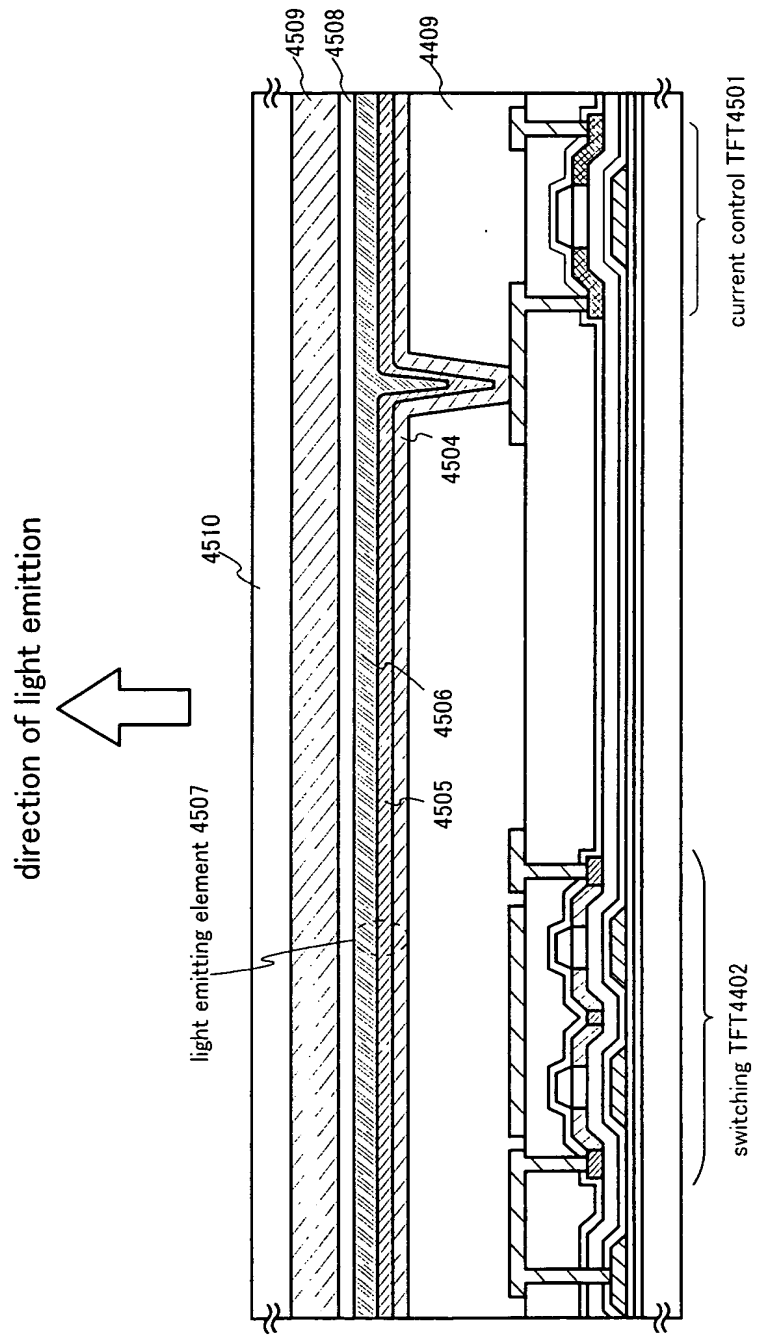
Fig. 16B





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Fig. 17



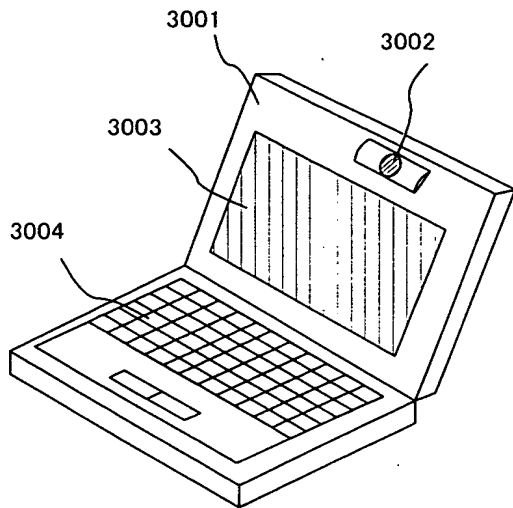


Fig. 18A

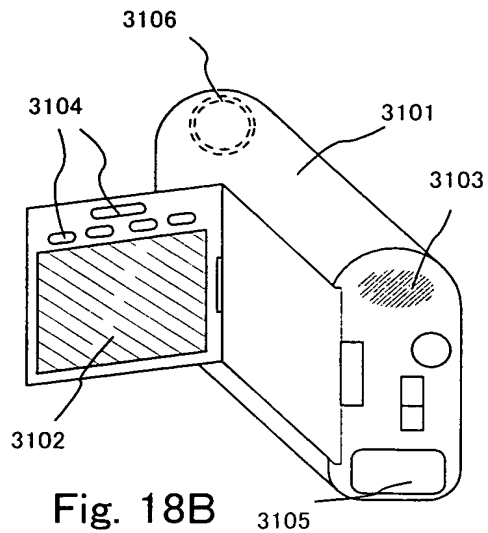


Fig. 18B

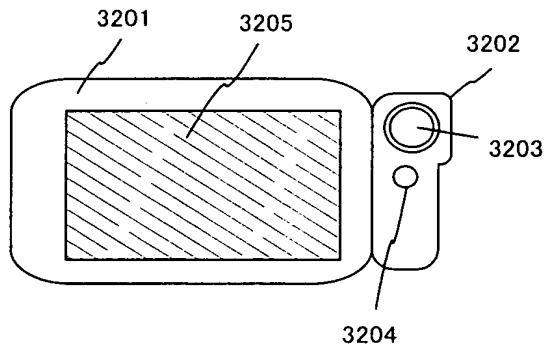


Fig. 18C

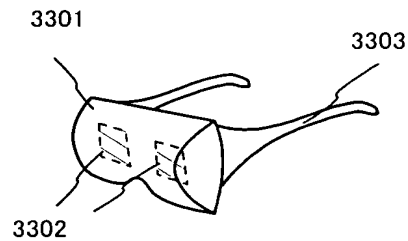


Fig. 18D

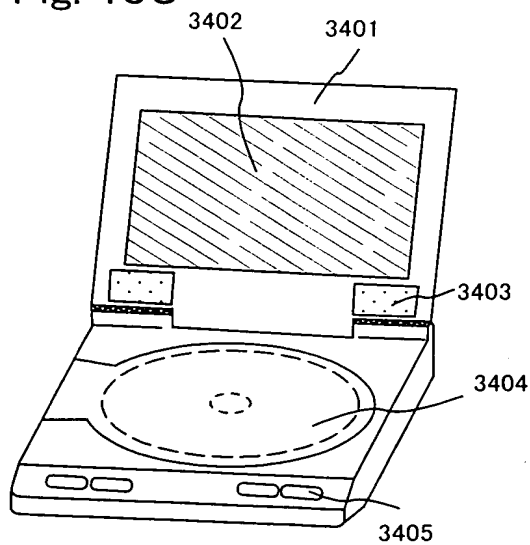


Fig. 18E

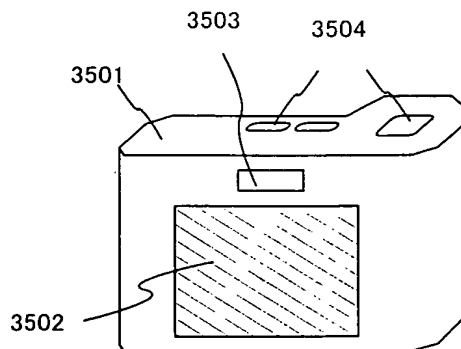


Fig. 18F

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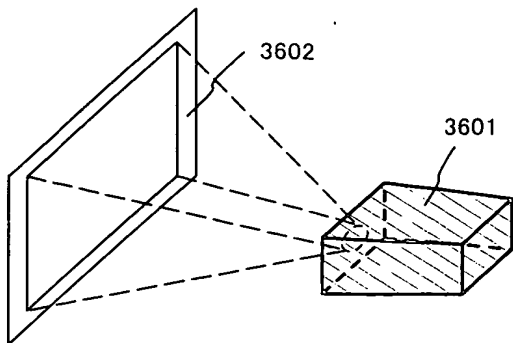


Fig. 19A

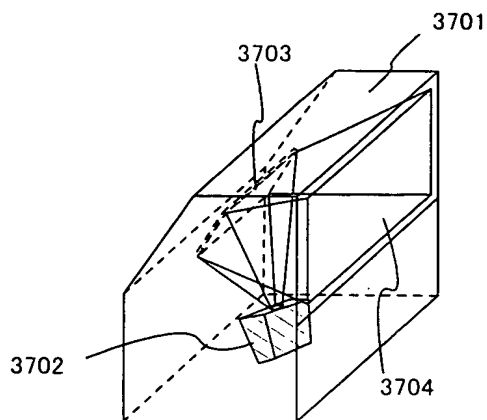


Fig. 19B

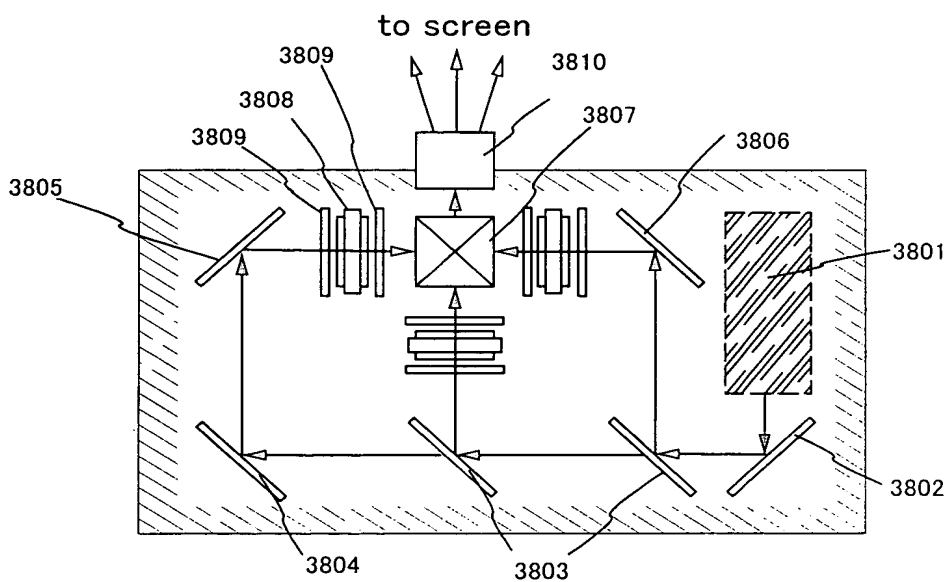


Fig. 19C

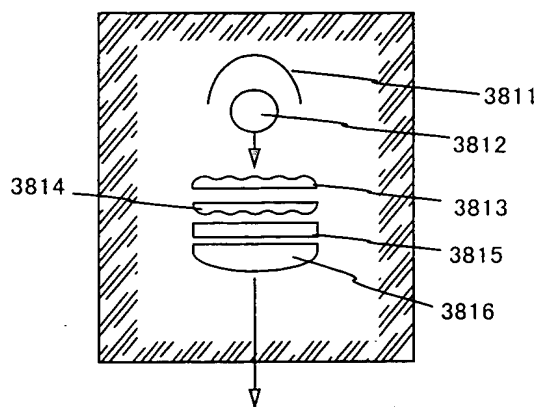


Fig. 19D

**Fig. 20B**

4004

4002

4005

4003

4001

4006

Figure 4 is a perspective view of a display device 400. The device includes a display panel 4101, a bezel 4102, and a base 4103. The display panel 4101 is shown with diagonal hatching.